IN THE SPECIFICATION:

Please amend the paragraph starting on page 5, line 7 as follows:

In an effort to accomplish this objective, in 1999 Dirksen et al. (see, US patent ~~application serial No. 09/407,532~~ no. 6,248,486, filed September 29, 1999, incorporated herein by reference) proposed a method for directly monitoring lens aberration from the printed wafers. According to Dirksen's method, the lens monitor comprises simple circular features on the reticle. More specifically, the circular feature is a chromeless feature that has been etched into the glass substrate of the reticle. The etched depth is typically $\lambda/2$ and the diameter is about (λ/NA), where NA is the numerical aperture of the projection lens. According to Dirksen, the method has proven to be effective. Further, the structure is simple and small enough to be readily placed throughout the entire exposure field.